Form 1449 (Modified)

Atty Docket No. Application No.:

NOVLP033X1/NVLS000498X1

Information Disclosure
Statement By Applicant

Lee et al.
Filing Date
Group
August 26, 2003

U.S. Patent Documents

			U.S. I atel	at Documents_			
Examiner						Sub-	Filing
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Examiner		Document	Publication	Country or		Sub-	Trans	ation
Initial	No.	No.	Date	Patent Office	Class	class	Yes	No

Other Documents

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Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication						
	C1	Levy et al., "Deposition of Tungsten Nitride", Novellus Systems, Inc., filed						
a		December 16, 2005, Application No. 11/305,368, pages 1-39.						
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Examiner		Chury a Date Considered 7/11/06						
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form 1449 (Modified)

Atty Docket No. NOVLP033X1/NVLS-

Application No.: 10/649,351

2498X1

Information Disclosure Statement By Applicant Applicant: Lee et al.

Group

(Use Several Sheets if Necessary)

Filing Date August 26, 2003

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а	C1	U.S. Office Action mailed May 17, 2006, from U.S. Application No. 10/984,126 [NOVLP058D1/NVLS-2732D1].				
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.